ABSTRACT OF THE DISCLOSURE

A method of fabricating a liquid crystal display using a negative photo-resist. A passivation layer covering a thin film transistor, a data line, and a gate line is formed on a transparent substrate. The passivation layer is patterned to define a contact hole that exposes a drain electrode. A transparent conductive film in electrical contact with the drain electrode via the contact hole is then formed on the passivation layer. A negative-type photoresist is coated on the transparent conductive film. The transparent conductive film is then exposed with an image of the desired pixel electrode. The negative-type photoresist is then developed to expose portions of the transparent conductive film over a data line, a gate line, and the area of the thin film transistor area. The exposed transparent conductive film is then etched.